## VIA FACSIMILE NO. (703) 872-9310

PATENT MIC04 P-106

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Examiner

G. Goudreau

Group

1763

Applicant

Imad Mahawili, PhD

Serial No.

09/488,309

Filed

January 20, 2000

For :

REACTOR WITH REMOTE PLASMA SYSTEM AND

METHOD OF PROCESSING A SEMICONDUCTOR SUBSTRATE

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

## CERTIFICATE OF FACSIMILE TRANSMISSION

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on <u>December 12</u>, 2002.

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PATENT MIC04 P-106

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**Examiner** 

George A. Goudreau

Group

1763

Confirmation No.

4253

**Applicant** 

Imad Mahawili, PhD

Serial No.

09/488,309

Filed

January 20, 2000

For

REACTOR WITH REMOTE PLASMA SYSTEM AND

METHOD OF PROCESSING A SEMICONDUCTOR

**SUBSTRATE** 

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

### RESPONSE

In response to the Office Action mailed December 4, 2002, having a three-month period of response ending March 4, 2003, Applicant wishes to amend his application as follows:

#### IN THE CLAIMS:

## Please amend Claim 20 as follows:



20. (Amended) The reactor according to Claim 22, wherein said gas injector comprises an elongate tube with a plurality of orifices through which the gas is injected into said processing chamber.

### **REMARKS**

Applicant has reviewed the Office Action and gratefully acknowledges the Examiner's indication of allowable subject matter. The amendments and remarks presented herein are fully supported by the application as originally filed. No new matter has been added.